- INFORMATION DISCLOSURE CITATION					Docket Number (Optional)		Application Number			
					YOR920020093US3 (16343ZY) Applicant(s)		Unassigned			
		(Use several sheets if necessa		Marie Angelopoulos, et al.						
					Filing Date Herewith		Group Art Unit Unassigned			
U.S. PATENT DOCUMENTS										
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME		CLASS	SUBCLASS	FILING IF APPRO		
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)										
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EXAMINER DOGOCO					DATE CONSIDERED 8/1/04					
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.										